



Fig. 4 (a) INPUT

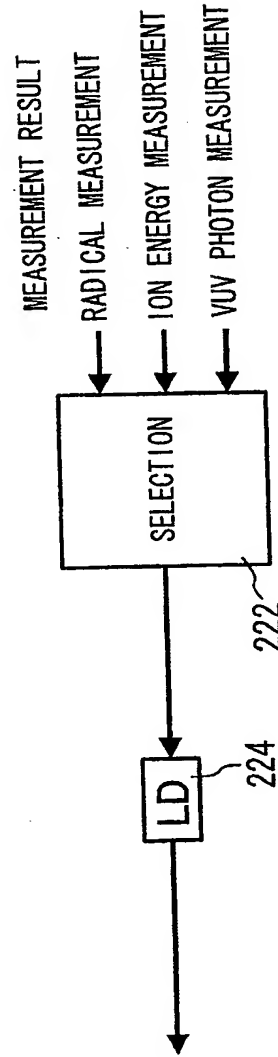
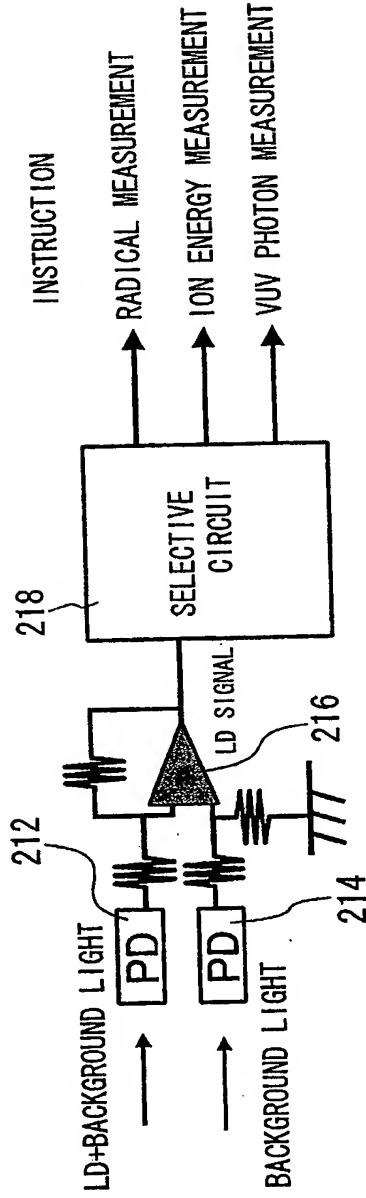


Fig. 4 (b) OUTPUT

# STRUCTURE OF ON-WAFER ION ENERGY ANALYZER

Fig. 7 (a)

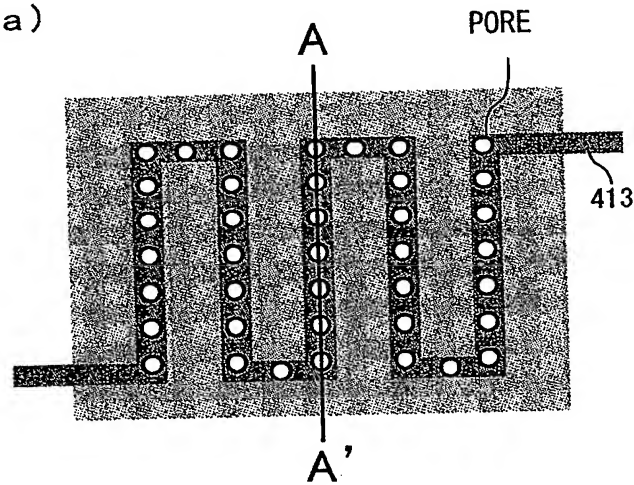
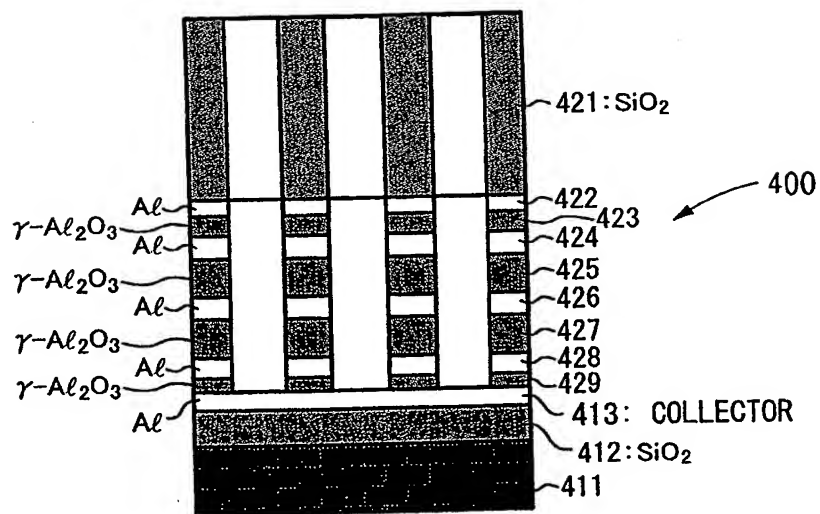
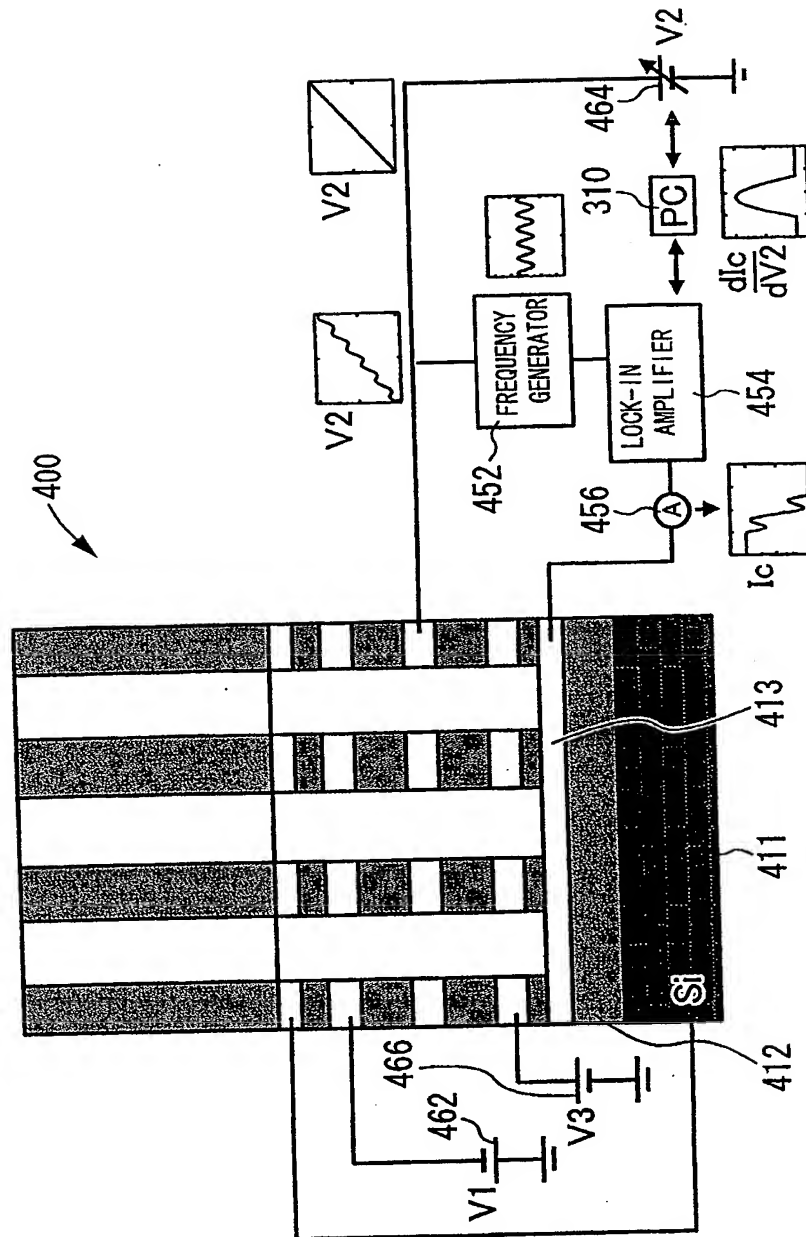


Fig. 7 (b)



**Fig. 8 MEASUREMENT SYSTEM OF ON-WAFER ION ENERGY ANALYZER**



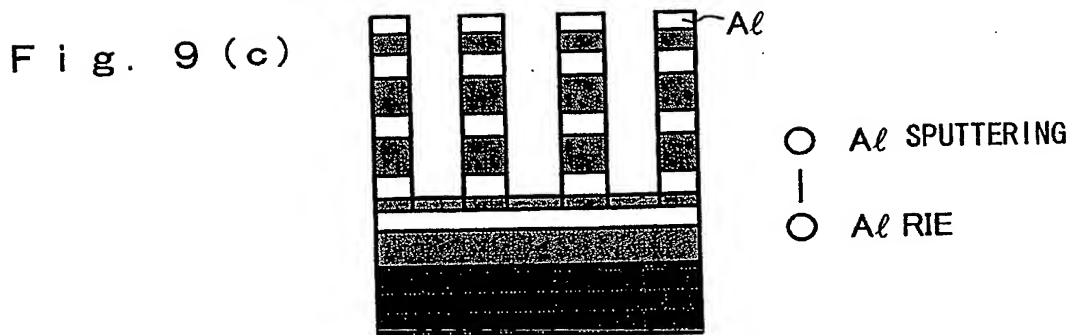
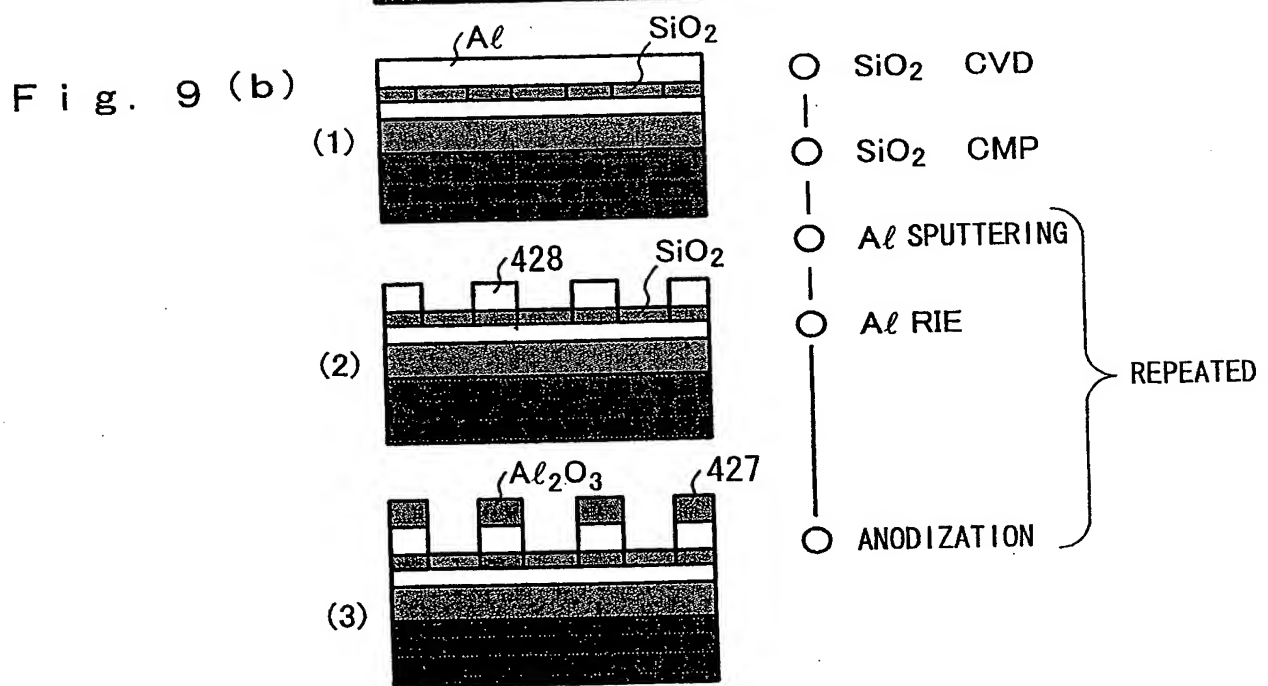
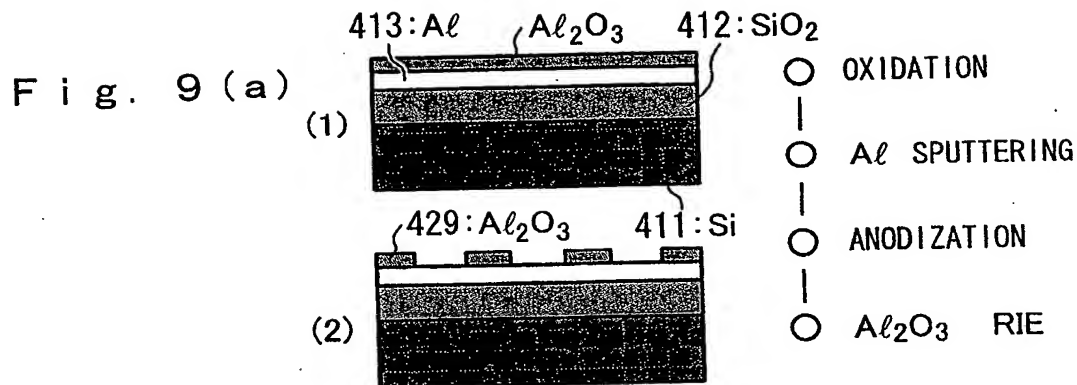


Fig. 10(d)

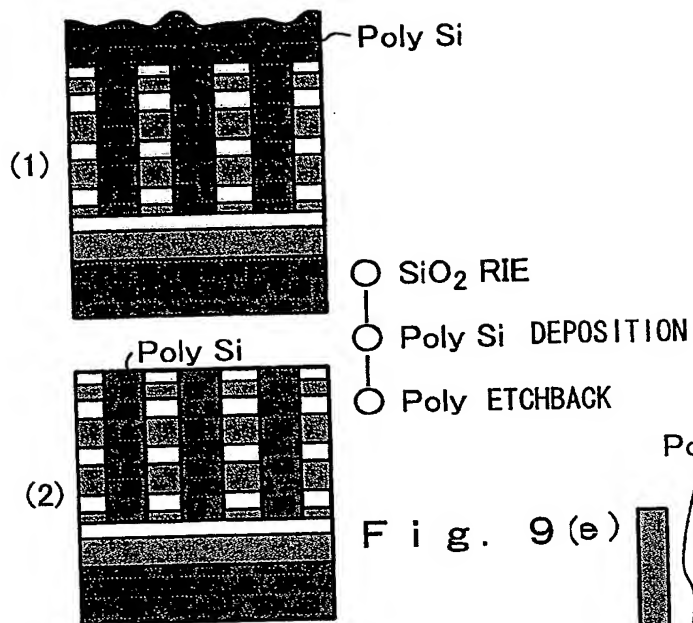


Fig. 9(e)

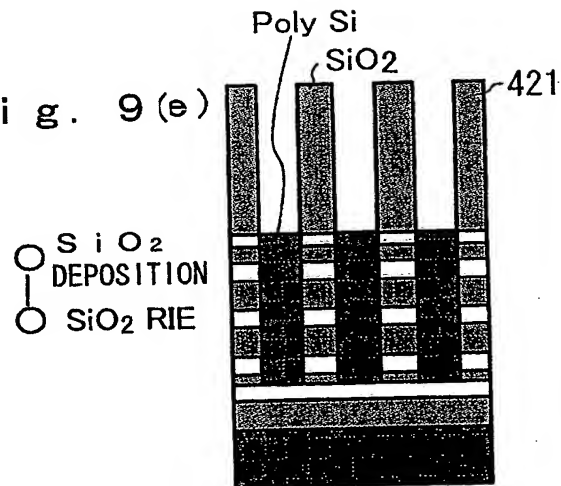
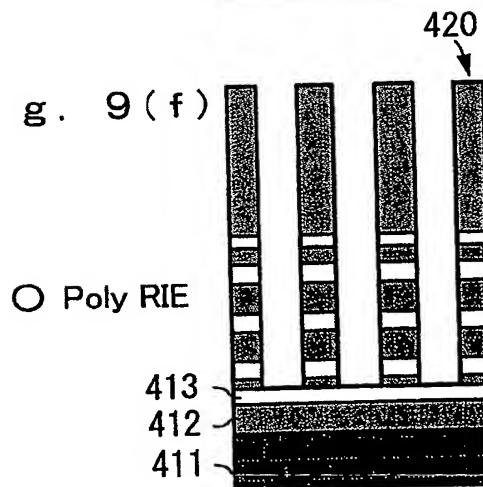


Fig. 9(f)



10/20

Fig. 11(a)

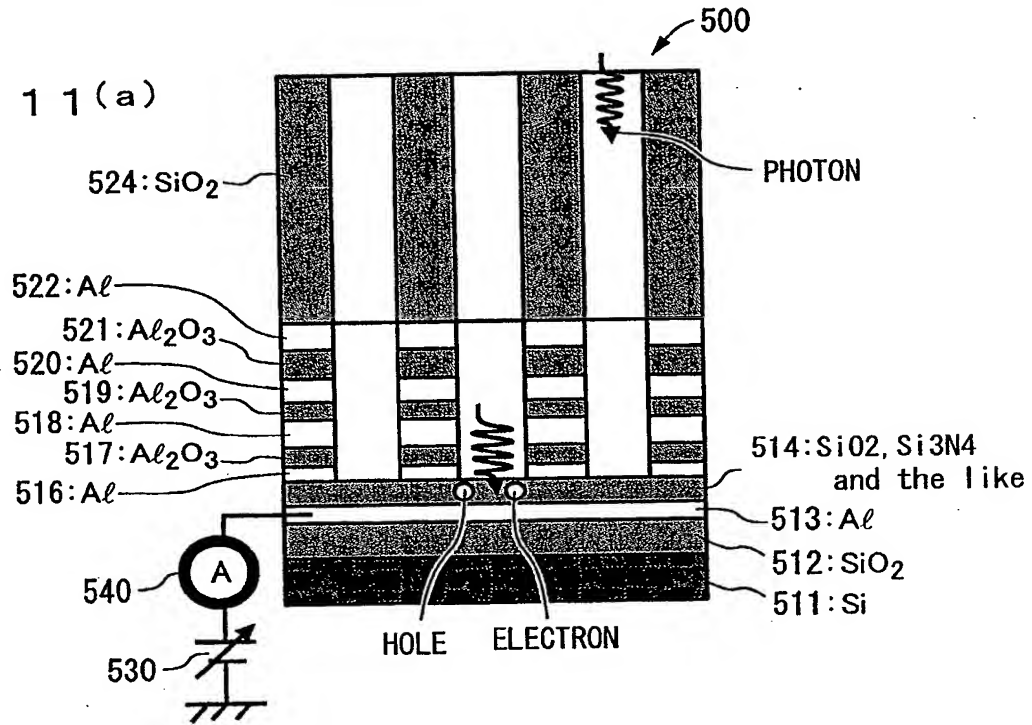
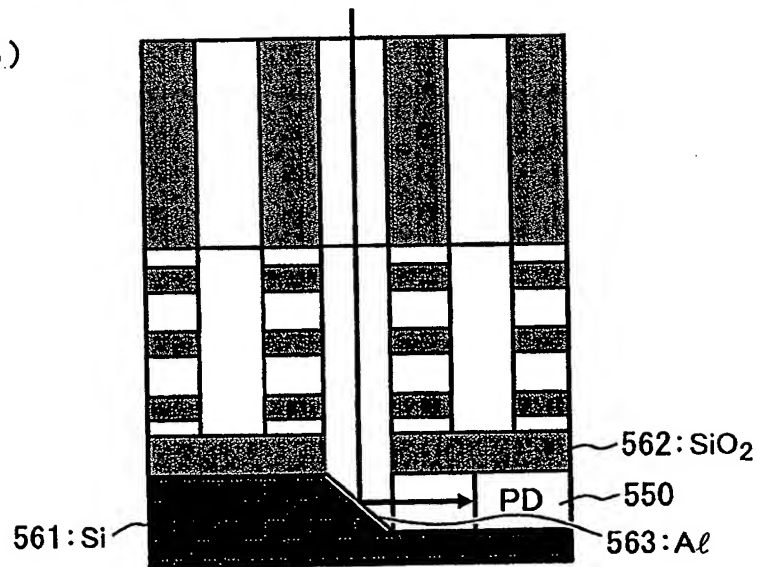


Fig. 11(b)



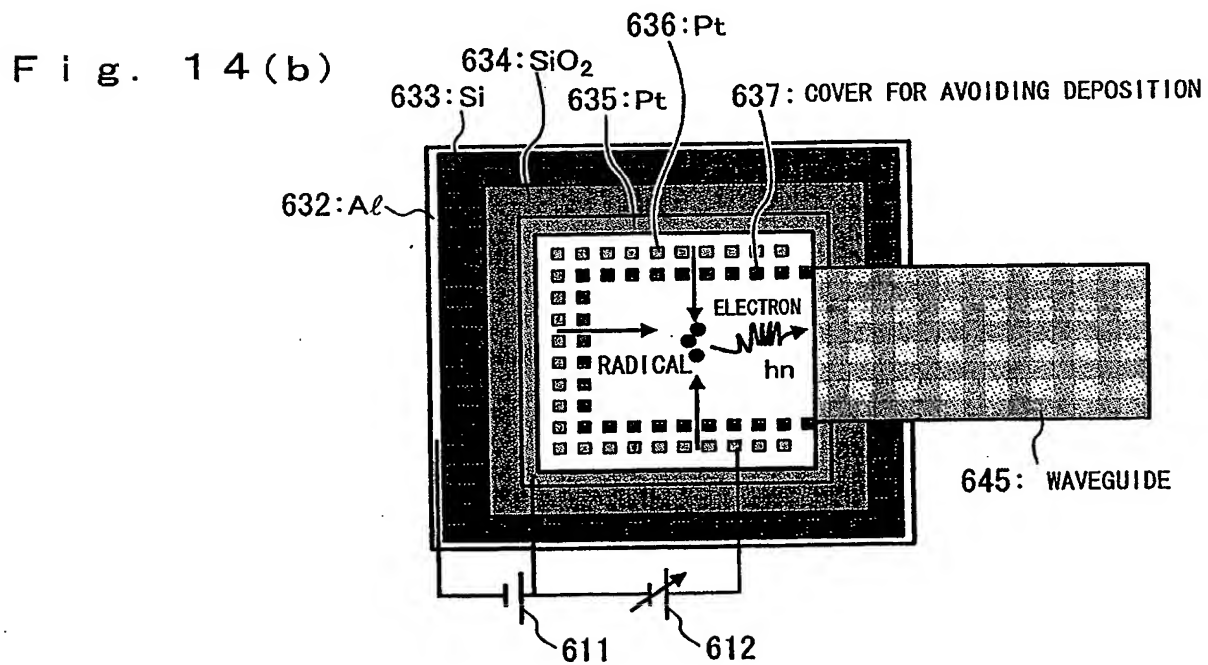
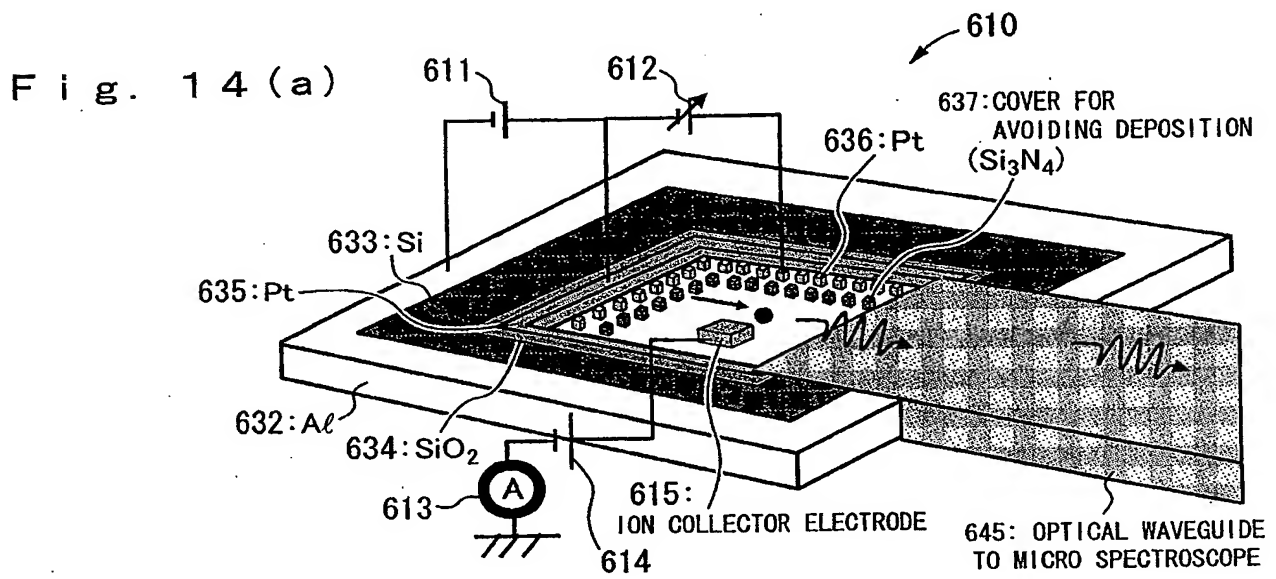


Fig. 15

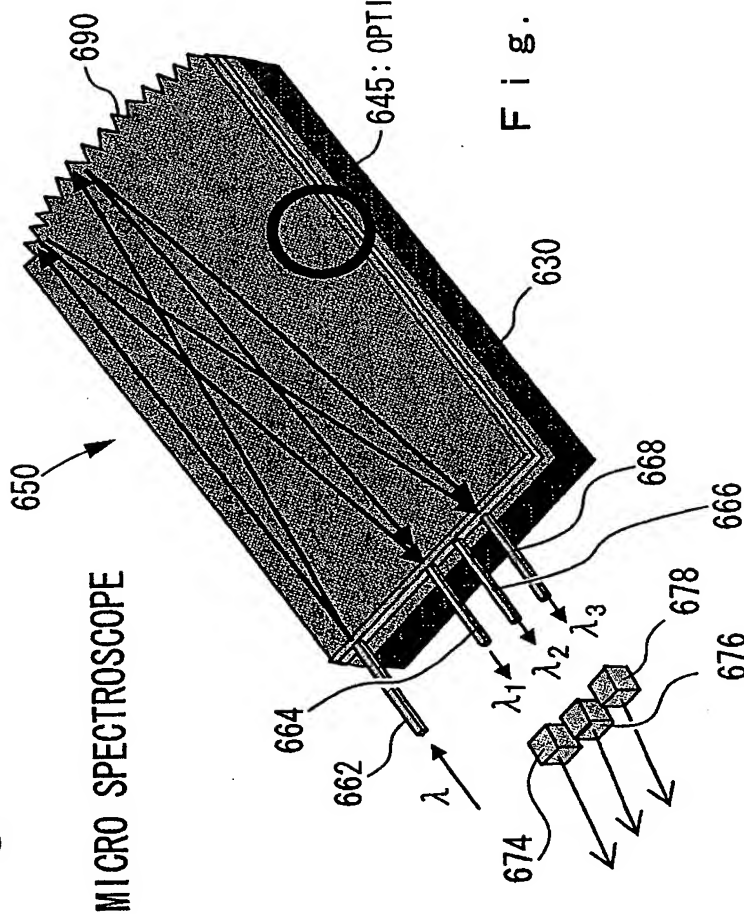


Fig. 15(a)

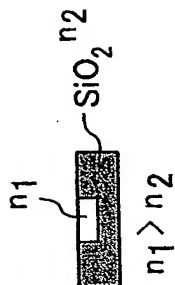
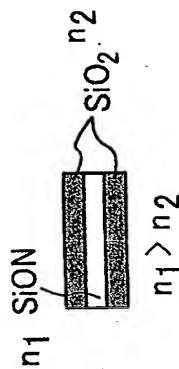


Fig. 15(b)





# MANUFACTURING PROCESS OF MICRO ION RADICAL ANALYZER(1)

Fig. 16(a) OXIDATION



Fig. 16(b) Si DEPOSITION, ETCHING



Fig. 16(c) Al VAPOR DEPOSITION, ETCHING



Fig. 16(d) SiO<sub>2</sub> DEPOSITION, ETCHING



Fig. 16(e) Pt DEPOSITION, PATTERNING

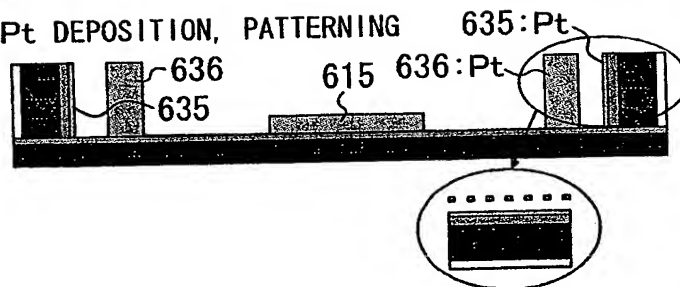
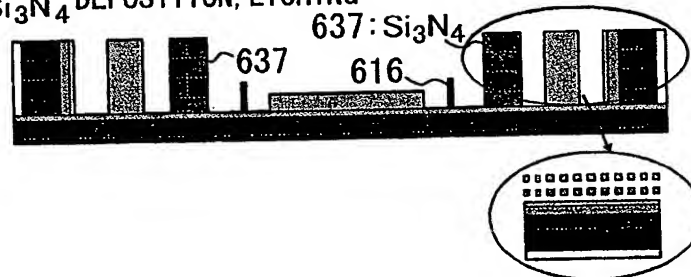


Fig. 16(f) Si<sub>3</sub>N<sub>4</sub> DEPOSITION, ETCHING



# MANUFACTURING PROCESS OF MICRO ION RADICAL ANALYZER (2)

